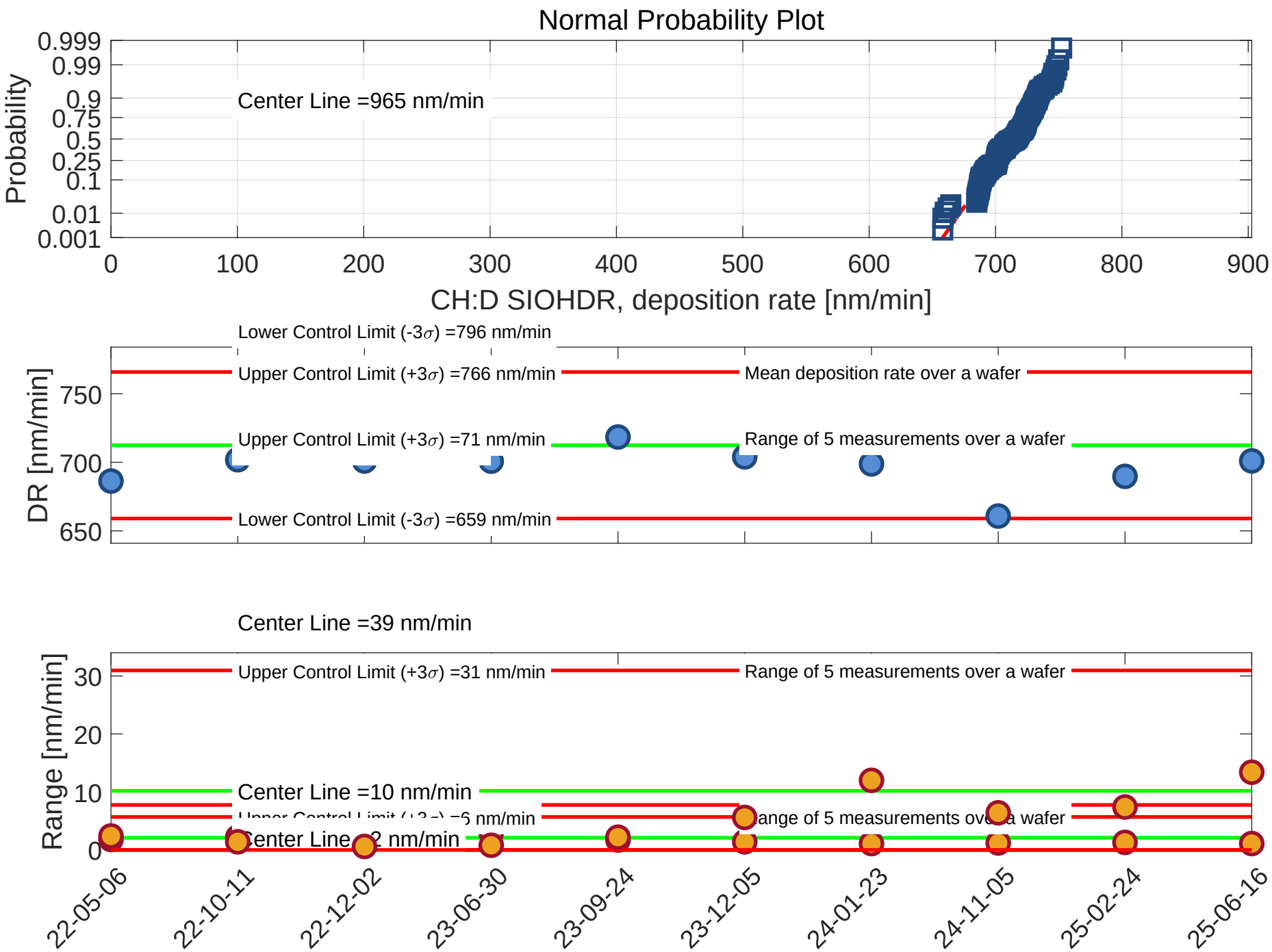
Normal Probability Plot
Probability
0.999
0.99
0.9
0.75
0.5
0.25
0.1
0.01
0.001
Center Line =965 nm/min
0
100
200
300
400
500
600
700
800
900
CH:D SIOHDR, deposition rate [nm/min]
Lower Control Limit (-3σ) =796 nm/min
Upper Control Limit (+3σ) =766 nm/min
Mean deposition rate over a wafer
Upper Control Limit (+3σ) =71 nm/min
Range of 5 measurements over a wafer
Lower Control Limit (-3σ) =659 nm/min
DR [nm/min]
750
700
650
Center Line =39 nm/min
Upper Control Limit (+3σ) =31 nm/min
Range of 5 measurements over a wafer
Center Line =10 nm/min
Range [nm/min]
30
20
10
0
22-05-06
22-10-11
22-12-02
23-06-30
23-09-24
23-12-05
24-01-23
24-11-05
25-02-24
25-06-16